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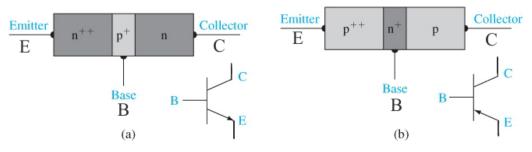


Figure 12.1 | Simplified block diagrams and circuit symbols of (a) npn and (b) pnp bipolar transistors.

Notation: ++ implies heavy doping concentration whereas + implies a moderate doping concentration.

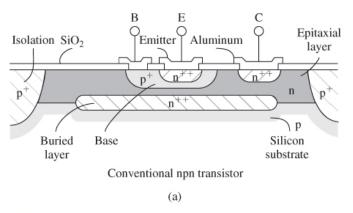


Figure 12.2 | Cross section of (a) a conventional integrated circuit npn bipolar transistor *(From Muller and Kamins [4].)* 

- > Buried  $n^{++}$  layer lowers resistance (and power loss).
- p<sup>+</sup> regions on either side provide isolation between transistors built on same wafer (or thick oxide regions can be used).
- > Note that emitter and collector are NOT symmetrical.

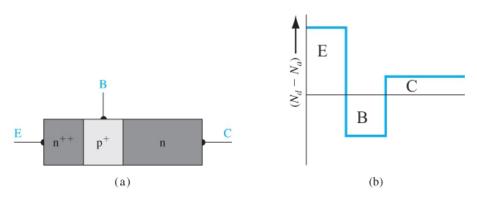


Figure 12.3 | Idealized doping profile of a uniformly doped npn bipolar transistor.

 $\gg N_d \sim 10^{19} \,\mathrm{cm}^{-3}$  for emitter.  $N_a \sim 10^{17} \,\mathrm{cm}^{-3}$  for base.  $N_d \sim 10^{15} \,\mathrm{cm}^{-3}$  for collector.